Our partner



Precision machinery company

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Point of use abatement systems

Wet Scrubber Model G-WS
Catalyst / Absorption Model GT

Precision machinery company Overseas office



Precision machinery company Japan office



[●] The product(s) described herein fall under "the goods listed in row 16 of the appended table 1 of the Export Trade Control Order of Japan", so in cases of export of su product(s), you need to confirm "use" and "purchaser and/or end-user" and, as case may be, obtain the approval of the Minister of Economy, Trade and Industry. (Plea confirm hese conditions on your own.) Furthermore, some of the product(s) fall under now 1 for the appended table 1 (listed tiems). In case of export of these list items, you are required to obtain the export license from the Minister of Economy, Trade and industry. For more information, please contact our sales office located ne

All specifications are subject to change without notice.







Wet scrubber model G-WS

Wet scrubber model designed for treating water-soluble and water-reactive gases. Inlet port is designed to restrain by-product clogging, which inherit unique EBARA technology of combustion type model selling for over 20 years.

Simple structures achieves reduced footprint and easy maintenance.

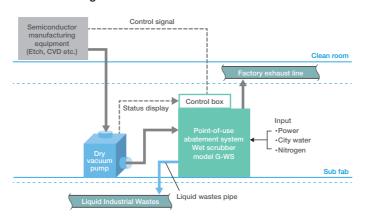
EBARA wet scrubber model G-WS provides high DRE, delivering abatement performance for semiconductor manufacturing process especially epitaxy, atomic layer deposition, metal etch and nitride process.

Model G-WS image flow

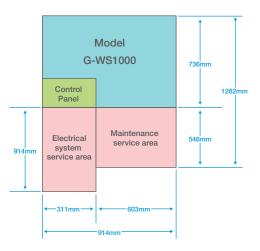


Gas outlet Cabinet ventilation Waste water water Nitrogen Recirculation pump vacuum pump

Installation image



Maintenance area



Specifications

Model		G-WS1000		
Maximum process flow rate (L/min)		1,000		
Number of inlet ports		Max. 4		
Dimensions (mm)		W914×D736×H1,727		
	Water flow rate (L/min)	1 - 10		
Utilities	Drainage flow rate (L/min)	1 - 10		
	Nitrogen (L/min)	15-50		
	Power supply	1.8-3.5kW, AC 200V, 50/60Hz,3 phases		
	Cabinet ventilation (m3/min)	0.5		
	Epi	HCI, DCS		
Main treatable gas	CVD	WF ₆ , NH ₃ , TiCl ₄ , BCl ₃ , CIF ₃ , SiF ₄ , Cl ₂ * ¹ , F ₂ * ¹		
	Etching	BCl ₃ , HCl, HF, HBr, SiF ₄ , Br ₂ *1, Cl ₂ *1, F ₂ *1		
	Asher	NH₃		
Gases that cannot be Treated		H ₂ , SiH ₄ , PH ₃ , GeH ₄ , CH ₄ , PFCs (CF ₄ , SF ₆ , NF ₃) etc.		

^{*1} Please contact us for details about gases conditions

Catalyst/Absorption Model GT

EBARA catalyst/absorption model GT enables the effective treatment of harmful and greenhouse gases chemically or physically without using carbon based fuels

PFCs gases that cannot be treated with ordinary dry bed abatement can be treated by EBARA fluorine-absorption type abatement.

Treatment technology

- Chemical reaction: Removed by chemical reactions of chemical agent Ex. (SiH₄ + 2MeO \rightarrow SiO₂ + 2H₂ + 2Me)
- Physical absorption: Removed by physical absorptions of chemical agent Ex. (Br₂, NH₃ absorb directly to dry bed)
- Ion exchange: Removed by ion exchange resin Cl₂ + R-N(CH₃)₂ → R-CH₂-(CH₃)2Cl-

High performance chemicals(Major category)

- Metallic oxide
- Crystalline aluminosilicates (Zeolite)
- Ion exchange resin
- Alkaline agent

Based on our vast accumulated knowledge over the past 20 years, EBARA offer the chemicals above according to shape, composition, and adsorption.

Specifications

Specifications							
Model			GTE, GTC, GTI				
Maximum process flow rate (L/min)			100				
Canister size (L)			85				
Canister I.D. (mm)			Ф 350				
	Single canister		W600 × D600 × H2,000				
Dimensions (mm)	Dual car	ister	W900 × D600 × H2,000				
Utilities	Nitrogen (L/min)		(Required for pneumatic valve action and purging the residual gas during canister exchange.)				
	Power supply		0.3~1.0kW, AC100/200V, 50/60Hz, 3 phases				
	Cabinet v	entilation (m3/min)	0.6				
	GTE	Etching	Acid gas PFCs gas Others	: BCl ₃ , Cl ₂ , HCl, HBr, Br ₂ , F ₂ , HF, SiF ₄ , etc. : C ₄ F ₆ , C ₅ F ₈ : CO, NF ₃ , H ₂ (Require heating)			
Main treatable gas	gтс	CVD	Flammable gas $:$ SiH ₄ , PH ₃ , AsH ₃ , B ₂ H ₆ , SiH ₂ Cl ₂ , NH ₃ , TEOS, etc Others $:$ N ₂ O (Require heating)				
	GTI	Ion implanting	Implanting gas : AsH ₃ , PH ₃ , BF ₃ , etc.				
Gases that cannot be Treated			PFCs gas	:CF ₄ , C ₄ F ₈ , C ₃ F ₈ , C ₂ F ₆ , CHF ₃ , CH ₃ F			

Optimized to abate particular chemical substances, by offering appropriate chemical solutions in accordance with process gases.

Various Line up No need for any water supply or drain equipment



fluorine-absorption model FDS



- ▶ Dry fixation of F* gas after PFCs gas decomposition does not require wastewater treatment.
- ▶Removal efficiency greater than 99% at maximum inflow gas volume at 250 slm
- ▶250 slm dual-cylinder type: Serial flow design of the canister greatly improves equipment uptime
- ▶100 slm single cylinder type: Easy to replace the existing dry bed type abatement

Specifications

Model	Dimensions (mm)	Canister (本)	Maximum flow rate (ℓ/min)
FDS100S	W600 × D600 × H2,000	1	100
FDS250*2	W1,520 × D1,000 × H2,150	2	250

^{*2 [}Products subject to list control]

This product falls under "goods listed in the Export Trade Control Order". An export license from the Minister of Economy, Trade and Industry is required for export.

^{*}Please contact us for details about service conditions.

^{*}If you are considering other than semiconductor manufacturing process, please contact us.